

# Discharge Pattern Discrimination in Vacuum Interrupter with Non-contact Measurement of Shield Potential

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## ABSTRACT

Vacuum interrupter has a composite insulation system. When an internal insulation fails, the discharge has complex and various patterns. Previously, based on the discharge development characteristics, we proposed a discrimination method for the discharge pattern in vacuum interrupter. We measured the applied voltage, anode current, and shield potential waveforms, respectively. From the analysis of the measured waveforms, we can estimate the discharge patterns and discharge path lengths. In this paper, a non-contact shield potential measurement was proposed when the shield potential cannot be measured directly. Furthermore, verification tests with this measurement method were conducted and the effectiveness of the discrimination method was confirmed.

Index Terms — Vacuum interrupter, floating electrode, discharge diagnostics, breakdown, surface flashover

## 1 INTRODUCTION

SINCE 1980s, vacuum circuit breakers (VCB) have been utilized worldwide in medium voltage system and distribution power networks [1]. The internal insulation problem of vacuum interrupters (VI) constrains the development of VCBs in the higher voltage systems [2-3]. Because VI has a composite insulation system, the discharge in VI has complex patterns for various discharge sites and paths. The discharge mainly occurs at insulation weakness points which may exist in VI, such as breakdown (BD) between vacuum gaps, surface flashover (FO) on insulator, and the combination patterns with BD and FO, as shown in Figure 1. Therefore, the discharge discrimination is significant for the efficient and reliable insulation design of VCB.

Previously, based on discharge development characteristics, we proposed a novel discrimination method of the discharge pattern in VI [4-5]. In this method, shield potential is a key factor for determining whether the discharge passed through the shield or not. However, it is not always possible to measure the shield potential directly in VI. Therefore, a new shield potential measurement method is necessary.

In this paper, we focus on the discharge discrimination with non-contact shield potential measurement method. An electrostatic probe was set on the outside of insulator of VI.

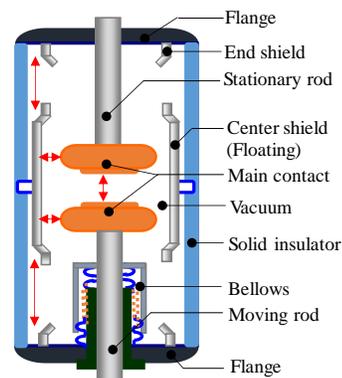


Figure 1. Possible discharge pattern in VI (red arrows represent possible discharge paths)

The shield potential can be calculated from the measured value by the electrostatic probe. Correspondingly, the discharge pattern discrimination method with the electrostatic probe was proposed and its effectiveness was verified.

## 2 DISCHARGE PATTERN DISCRIMINATION METHOD

By the measurement of electrical parameters (applied voltage, anode current, shield potential), we picked up the discharge features for each discharge pattern, respectively, and we proposed a discrimination flowchart as shown in Figure 2 which consisted of 3 steps [4-5]:

STEP 1: By the analysis of the features of applied voltage, anode current, and shield potential waveforms, we determine whether the discharge passed through the shield or not.

STEP 2: Based on the relation between the discharge development time and path length in the fundamental discharge characteristics from our database as shown in Figure 3, we estimate the possible discharge patterns and path lengths.

STEP 3: We discriminate the discharge site (insulation weakness) in consideration of the internal structure and dimension of VI.

The discharge mechanism in Figure 3 can be explained as follows: For the BD process in vacuum gap, according to the cathode plasma expansion model [6-8], the cathode plasma can be produced at the cathode surface and expand to the anode. The cathode plasma expansion velocity was calculated to be in the order of  $10^4$  m/s, which was determined by the electrode material, and independent of the potential difference between the cathode and the shield, i.e. electric field strength. BD development time  $T_{BD}$  depends on the gap length  $g$  monotonically, therefore, we can estimate the gap length from

the measurement of  $T_{BD}$  [9-10]. For the FO process on insulator, the discharge starts with the explosive electron emission on cathode surface. According to the electron-stimulated outgassing model [11-13], FO development time  $T_{FO}$  is proportional to  $V_{FO}^{-2}$  and  $T_{FO}$  increased with increasing surface distance  $d$  for a certain  $V_{FO}$  [9-10]. Based on the relation between  $T_{FO}$  and  $d$ , the surface distance can be estimated from the measurement of  $T_{FO}$  and  $V_{FO}$ . The discrimination success rate with the above method reached as high as 93% [4].

### 3 DISCRIMINATION METHOD WITH ELECTROSTATIC PROBE

#### 3.1 VI MODEL

Figure 4 shows the VI model for the discrimination of discharge pattern. The VI model consisted of upper electrode (u), cathode (c), anode (a), lower electrode (l), shield (s) and insulator (i), which can simulate the actual internal structure of VI. The upper and lower electrodes had plane shape and were made of stainless steel. The cathode and the anode had plane shape and were made of copper. The cathode and the anode were connected with the upper electrode and the lower electrode, respectively. The floating electrode as a shield was placed on the center of insulator. The shield was made of stainless steel with the dimension of 120 mm × 60 mm × 2 mm. The insulator was alumina ceramic (Al<sub>2</sub>O<sub>3</sub>, purity: 92%) with the dimension of 150 mm × 150 mm × 5 mm. The upper and lower electrodes were contacted with the insulator.

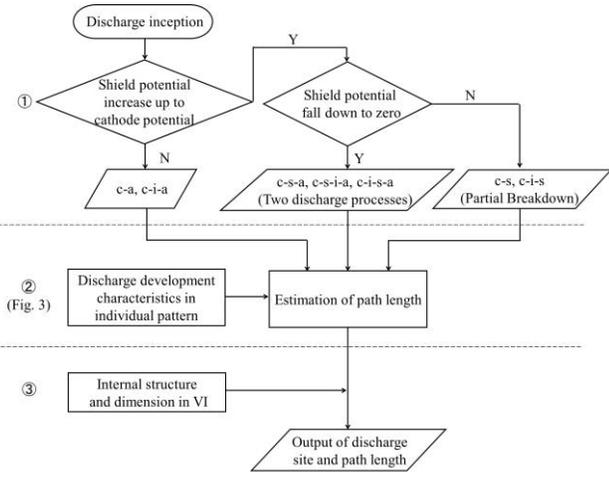


Figure 2. Discrimination flowchart

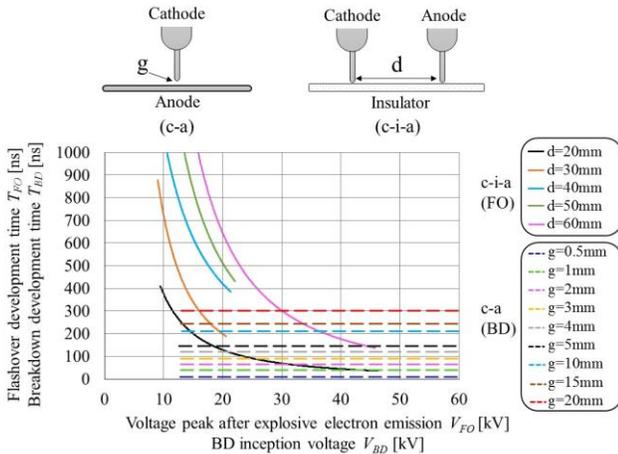


Figure 3. Fundamental discharge development characteristics for BD and FO

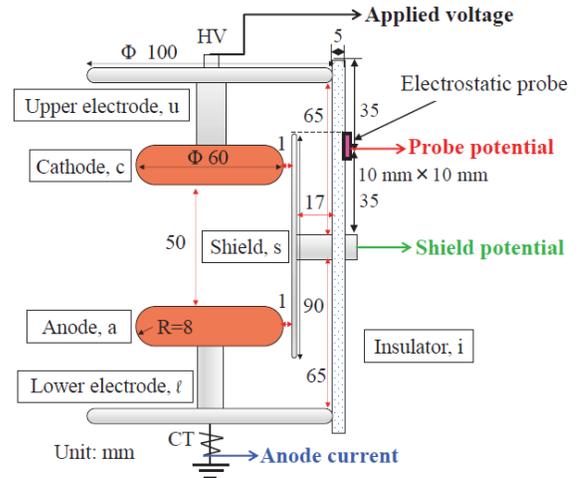


Figure 4. VI model with an electrostatic probe.

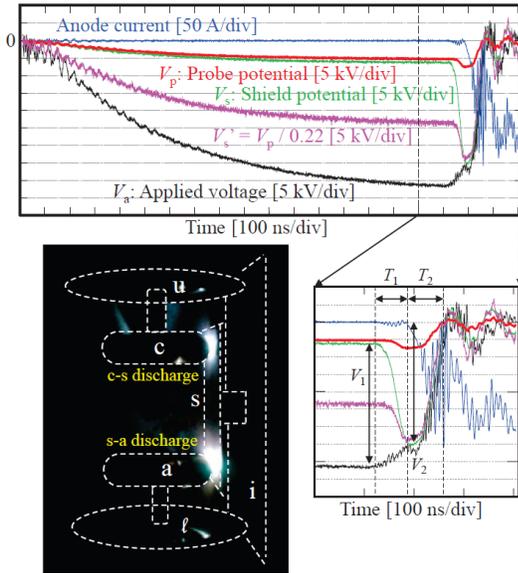
We measured the applied voltage waveform with a voltage divider (1/45900), the anode current with a high frequency current transformer (1-20 MHz). A metal sheet with the dimension of 10 mm × 10 mm as an electrostatic probe was set on outside of the insulator behind the shield to measure the shield potential indirectly. At the same time, the shield potential was measured by a high voltage probe (input impedance: 100 MΩ) directly. The VI model was set in a vacuum chamber with  $10^{-5}$  Pa. The impulse generator

provided a negative standard lightning impulse voltage (1.2/50  $\mu$ s). These waveforms were acquired by a digital oscilloscope (2.5 GHz, 40 GS/s). In addition, still images of discharge were captured with a digital camera to check the discharge patterns.

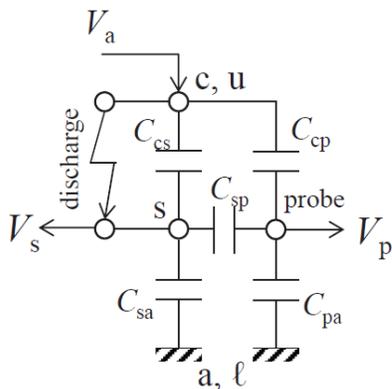
### 3.2 SHIELD POTENTIAL DETERMINATION

Figure 5 shows discharge waveforms and light emission for a discharge through cathode-shield-anode (c-s-a) at the applied voltage  $V_a = -43$  kV<sub>peak</sub>. The discharge process is as follows: Firstly, the discharge between cathode and shield occurred ( $V_1$ : discharge voltage of the first discharge,  $T_1$ : discharge development time of the first discharge). Then, the discharge between shield and anode occurred ( $V_2$ : discharge voltage of the second discharge,  $T_2$ : discharge development time of the second discharge), resulting in the whole discharge through cathode-shield-anode (c-s-a). Due to the cathode and the shield were shorted by the first discharge, the shield potential  $V_s$  jumped up to the applied voltage  $V_a$ . The discharge via shield was discriminated and confirmed by the light emission.

Before the discharge, as shown in Figure 6, the ratio



**Figure 5.** Discharge waveforms and light emission for c-s-a discharge ( $V_a = -43$  kV<sub>peak</sub>).



**Figure 6.** Equivalent circuit to calculate  $V_p / V_s$ .

between the probe potential  $V_p$  and the shield potential  $V_s$  was determined by the capacitance distribution between the electrode gaps as follows:

$$\frac{V_p}{V_a} = \frac{C_{cs} C_{sp} + C_{cp} (C_{cs} + C_{sp} + C_{sa})}{C_{sp} (C_{cs} + C_{sa}) + (C_{cp} + C_{pa}) (C_{cs} + C_{sp} + C_{sa})} \dots (1)$$

$$\frac{V_s}{V_a} = \frac{C_{cp} C_{sp} + C_{cs} (C_{cp} + C_{sp} + C_{pa})}{C_{sp} (C_{cp} + C_{pa}) + (C_{cs} + C_{sa}) (C_{cp} + C_{sp} + C_{pa})} \dots (2)$$

where  $C_{cp}$  is capacitance between cathode and probe,  $C_{pa}$  is capacitance between probe and anode,  $C_{cs}$  is capacitance between cathode and shield,  $C_{sa}$  is capacitance between shield and anode,  $C_{sp}$  is capacitance between shield and probe. The capacitances were measured by LCR meter. According to equations (1) and (2),  $V_p/V_s = 94\%$  before the discharge was calculated and verified in Figure 5.

After the first discharge between cathode and shield,  $V_p/V_s$  was determined by a new capacitance distribution between the electrode gaps, because the cathode and the shield were shorted, as follows:

$$\frac{V_p}{V_s} = \frac{C_{cp} + C_{sp}}{C_{cp} + C_{sp} + C_{pa}} \dots (3)$$

According to equation (3),  $V_p/V_s = 22\%$  after the first discharge was calculated and verified in Figure 5.

Therefore, the relation between  $V_p$  and  $V_s$  is clear in the discharge process. Conversely, we can determine the shield potential from the equation  $V_s' = V_p/22\%$  so as to discriminate the discharge pattern, even if we cannot measure the shield potential directly.

### 3.3 VERIFICATION TESTS

In order to confirm the effectiveness of the discharge pattern discrimination method with an electrostatic probe, we executed iterative verification tests based on the discrimination flowchart in Figure 2. As shown in Table 1, the tests results revealed that the discrimination success rate with an electrostatic probe was almost the same as that by direct measurement of the shield potential. The details of discrimination process for c-s-a discharge pattern are shown as follows:

**Table 1.** Verification tests results

Discharge pattern	c-s	c-s-a	u-i-s-i-l	c-s-i-l	not available	Total
Discharge site in VI Model					—	—
Frequency (by shield)	2	6	3	1	2	14
Frequency (by probe)	2	6	3	0	3	14

STEP 1:

Firstly, in Figure 5, we focus on the waveform  $V_s'$  that was calculated from  $V_p$  ( $V_s' = V_p/22\%$ , according to previous section). Because the calculated shield potential  $V_s'$  jumped up to the instantaneous cathode voltage and fell down to 0 V together with the cathode voltage, it can be determined that the discharge passed through the shield and short-circuited between the cathode and the anode. Such a two-step change in discharge waveforms means that this discharge pattern has two processes, we call them the first process and the second

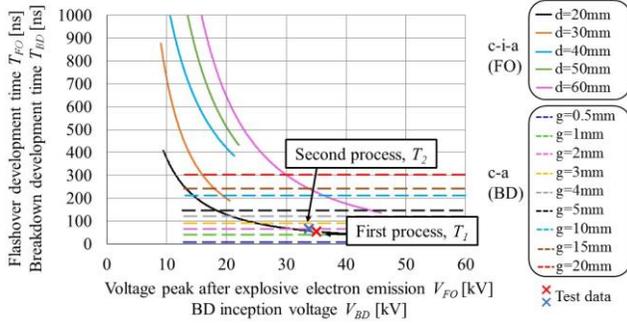


Figure 7. Discharge development characteristics for c-s-a pattern ( $V_a = -43$  kV<sub>peak</sub>).

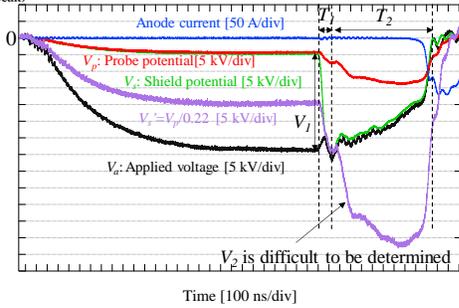


Figure 8. Discharge waveforms and light emission for c-s-i-l discharge ( $V_a = -34$  kV<sub>peak</sub>).

process, respectively.

STEP 2:

For the first process in Figure 5, the discharge development time  $T_1$  was 60 ns and the discharge voltage  $V_1$  was 35 kV. For the second process, the discharge development time  $T_2$  was 70 ns and the discharge voltage  $V_2$  was 33 kV. The sets of ( $V_1, T_1$ ) and ( $V_2, T_2$ ) were plotted in Figure 3, as shown in Figure 7.  $T_1$  is consistent with the BD development time in about 1 mm gap,

and also consistent with the FO development time in the creepage distance of about 20 mm.

STEP 3:

By the consideration of the internal structure and dimension of the VI model in Figure 4, the first process can be identified as discharge between the cathode and the shield (c-s). The relationship between  $V_2$  and  $T_2$  was also consistent with BD in 1 mm gap and FO in 20 mm creepage distance. The same reason as the first process, the second process can be determined as BD between the shield and the anode (s-a) with 1 mm gap. From the light emission of discharge in Figure 5, we confirmed that the discharge occurred at c-s and s-a, i.e. c-s-a, which is consistent with the above discrimination result.

In some cases, such as c-s-i-l pattern near the electrostatic probe in Figure 8, due to the influence of flashover channel potential, the shield potential was not determined by the capacity distribution between the electrode gaps. Therefore, it was difficult to evaluate  $V_2$  and resulted in the discrimination failure. However, this problem can be solved by using an array of electrostatic probes on the insulator surface of VI, as shown in Figure 9, where some probes would detect the shield potential, irrespective of the internal flashover path. It is also expected to discriminate and identify the flashover path, which might be better than the direct measurement of shield potential. For the application of this technique to an actual vacuum interrupter, the size and position of the electrostatic probe may affect the accuracy of shield potential measurement, as estimated by equations (1)-(3), due to the change of the capacitances distribution of electrode gaps. Therefore, the size and position of the electrostatic probe should be checked carefully.

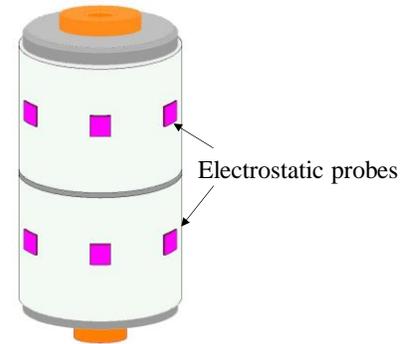


Figure 9. Prospective arrangement of electrostatic probes on the insulator surface of VI.

## 4 CONCLUSION

In order to discriminate the discharge pattern in vacuum interrupters, based on the discharge development characteristics, we proposed a novel discrimination method of the discharge pattern in vacuum. In this discrimination method, the measurement of electrical parameters (applied voltage, anode current, shield potential) is necessary. For the case that the shield potential cannot be measured directly, we developed

a new non-contact measurement method of the shield potential with an electrostatic probe. Furthermore, verification tests using this measurement method were conducted and the effectiveness of the discrimination method was verified. This work will contribute to the identification of the insulation weak points in vacuum interrupters as well as to the advanced and reliable insulation design of vacuum circuit breakers.

## REFERENCES

- [1] Paul G. Slade: "The vacuum interrupter: Theory, Design, and Application", CRC press, pp.1-6, 2007.
- [2] H. Okubo, H. Kojima, K. Kato, N. Hayakawa and M. Hanai, "Advanced Electrical Insulation Techniques for Higher Voltage Vacuum Interrupters", CIGRE B3/D1 Colloquium, No.218 (2013).
- [3] L. T. Falkingham, "Vacuum Interrupter Design for HV and VHV Applications", the 22nd Int'l. Sympos. Discharges and Electr. Insulation in Vacuum, pp.204-207, 2006.
- [4] F. Kong, H. Kojima, M. Tsukima, T. Kimura, and N. Hayakawa: "Discharge Pattern Discrimination for Composite Insulation System in Vacuum interrupter", XXVIIIth Int. Symp. on Discharges and Electrical Insulation in Vacuum, Sep.18-23, 2016
- [5] F. Kong, H. Kojima, T. Kimura, M. Tsukima, and N. Hayakawa.: "Discharge Pattern Discrimination for Composite Insulation System in Vacuum", IEEJ Transactions on Fundamentals and Materials, Vol.136, No.9, pp.594-602 (2016) (in Japanese)
- [6] Gennady A. Mesyats and D.I. Proskurovsky, Pulsed Electrical Discharge in Vacuum, 1st ed., Springer-Verlag, pp.118-135, 1989.
- [7] E. Hantzsche, "Theory of the Expanding Plasma of Vacuum Arcs", J. Phys. D: Appl. Phys., Vol. 24, pp. 1339-1353, 1991.
- [8] I. I. Beilis, "State of the Theory of Vacuum Arcs", IEEE Trans. Plasma Sci., Vol. 29, No. 5, pp. 657-670, 2001.
- [9] F. Kong, Y. Nakano, H. Kojima, N. Hayakawa, T. Kimura, and M. Tsukima: "Discharge Characteristics for Various Discharge Patterns under Negative Lightning Impulse Voltage in Vacuum", IEEE Transactions on Dielectrics and Electrical Insulation, Vol. 23, No.2, pp. 813-818 (2016)
- [10] F. Kong, Y. Nakano, H. Kojima, N. Hayakawa, T. Kimura, and M. Tsukima: "Discharge Characteristics of Composite Insulation System with Floating Electrode and Solid Insulator in Vacuum", IEEE Transactions on Dielectrics and Electrical Insulation, Vol. 23, No.2, pp. 1219-1225 (2016)
- [11] R. A. Anderson and J. P. Brainard, "Mechanism of Pulsed Surface Flashover Involving Electron-stimulated Desorption", J. Appl. Phys., Vol. 51, No. 3, pp. 1414-1421, 1980.
- [12] A. S. Pillai and R. Hackam, "Surface Flashover of Solid Dielectric in Vacuum", J. Appl. Phys., Vol. 53, No. 4, pp. 2983-2987, 1982.
- [13] A. A. Neuber, M. Butcher, H. Krompholz, L. L. Hatfield and M. Kristiansen, "The Role of Outgassing in Surface Flashover under Vacuum", IEEE Trans. Plasma Sci., Vol. 28, No. 5, pp. 1593-1598, 2000.



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